

1 Effects of Spatial Sensitivity on Mass Sensing with Bulk Acoustic Mode Resonators

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8 Abstract

9 The spatial sensitivity of bulk acoustic mode resonators can influence calibrations when they
10 are implemented as accurate mass sensors of surface-bound particles. A new spatial
11 sensitivity model based on images of the resonator surface is introduced from early
12 principles. The adsorption of particles was studied empirically by repeatedly drying particle
13 laden droplets on the surface of two 3.14 MHz bulk acoustic mode resonators. Theoretical
14 and experimental results were compared to identify three scenarios over the course of
15 consecutive droplet evaporation with varying spatial sensitivity influences. Examining
16 different surface treatments for the resonators revealed the hydrophilic surface to have a
17 higher rate of particle stacking and conglomeration.

18 *Keywords:* Spatial Sensitivity; Bulk Acoustic Wave (BAW); Bulk Acoustic Mode Resonator;
19 Particulate Mass Sensor; MEMS; Mathematical Modelling.

20 Highlights:

- 21 • Several spatial sensitivity models are introduced for particulate mass sensing.
 - 22 • Comparison with experiments using evaporated particulate laden water droplets.
 - 23 • Three sensitivity scenarios were identified for repeated mass addition.
 - 24 • Hydrophilic surface shows propensity towards particle stacking and conglomeration.
-

25 1. Introduction

26 Micromechanical resonators have seen increased use in a range of inertial [1], temperature
27 [2], and mass sensing [3] applications. Many mass sensing applications focus on uniform
28 depositions [3,4], but a niche exists for dispersed aerosol particle sensing for environmental
29 and health applications, with potentially non-uniform mass deposition. Atmospheric aerosols
30 from anthropogenic or natural sources are key components of the climate system as they
31 affect directly or via cloud processes the radiative budget of the atmosphere [5]. Negative
32 health impacts of aerosol particles are well established based on correlations with particle
33 mass and morbidity or mortality statistics [6].

34 Most current small-scale systems use optical methods [7] for detecting particles that cannot
35 detect particles below 100 nm in diameter [8] (which may be responsible for most of the
36 observed health effects [9,10]) and are typically expensive, complex, and can only estimate
37 particle mass based on diameter. A desire for real time mass measurements led to the
38 implementation of mechanical resonators as mass sensors. Early work by Chuan [11]
39 replacing traditional impactor collection filters with a quartz crystal microbalance has since
40 been extended to other micromechanical resonators. Black *et al.* [12] and Paprotny *et al.* [13]
41 both used thin-film bulk acoustic resonators to measure particles collected via thermophoresis
42 while Mehdizadeh *et al.* [14] employed thermally actuated resonators as part of a traditional
43 impactor design. The above resonators have shown to offer highly sensitive detection of

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44 particulate mass, but certain resonator geometries are susceptible to spatial variations in
45 sensitivity [15,16] that must be accounted for when interpreting the resonator output.

46 A resonator can be modelled as a one-dimension mass-spring-damper system where the
47 resonant frequency (f_0) is related to the effective mass (M_{eff}) and stiffness (K_{eff}) by:

$$48 \quad f_0 = \frac{1}{2\pi} \sqrt{\frac{K_{\text{eff}}}{M_{\text{eff}}}} \quad \text{Eq. 1}$$

49 Mass addition to the device (effectively an increase in M_{eff}) results in a detectable frequency
50 shift providing a means of mass sensing. Two of the most common resonator topologies are
51 the flexural and bulk acoustic mode resonators [17]. This study focuses on bulk acoustic
52 mode resonators due to their higher quality factors [18] as particle adsorption may degrade
53 signal quality.

54 Uniform mass addition has previously been shown [19] to follow a general sensitivity model
55 based on Sauerbrey's principle for a frequency shift Δf and mass addition Δm (assuming no
56 change in stiffness):

$$57 \quad \Delta f = -\frac{f_0}{2M_{\text{eff}}} \Delta m \quad \text{Eq. 2}$$

58 The simple model, however, fails to account for the spatial sensitivity of the resonator.
59 Previous studies by Campanella *et al.* [20] have modelled spatial dependencies in thin-film
60 bulk acoustic-wave resonators (FBARs). Their results highlight the importance of spatial
61 sensitivity in microresonators while also discussing the influence of deposition area. The
62 following study develops a spatial sensitivity model in the context of particulate adsorption
63 from a liquid medium for the purpose of mass sensing using bulk acoustic mode resonators.
64 The model can be used to study the mass of particles in liquid biological samples or to study
65 the deposition of particles from a gaseous medium (by removing the influence of the liquid)
66 for more relevant atmospheric measurement studies. The theoretical model was compared
67 with experimental results using square bulk acoustic mode single-crystal silicon
68 microelectromechanical systems (MEMS) resonators to show three different stages of particle
69 adsorption based on residue formation after evaporation. Work focused on the symmetric
70 square-extensional mode but the method can be expanded to different geometries and modes.

71 **2. Description of resonators**

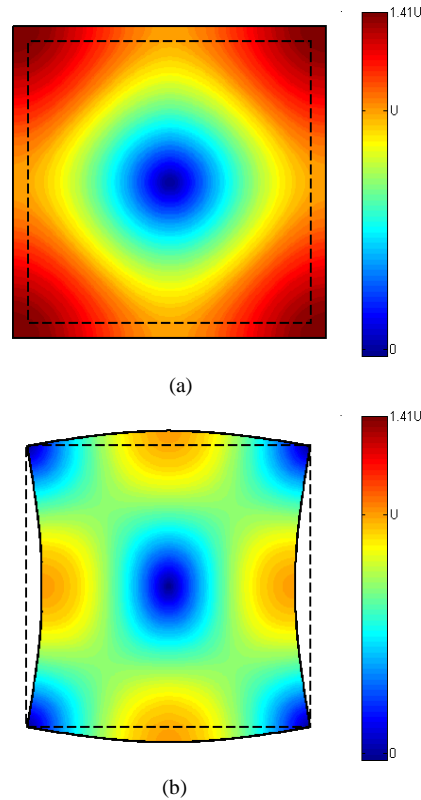
72 Bulk mode resonators are defined to have full body contraction and extension. For a square,
73 corner-anchored resonator the two commonly excited in-plane vibration modes are the
74 square-extensional (SE) and wine glass (WG) – or Lamé – modes. The SE mode is
75 characterised by symmetric extension/contraction along orthogonal axes producing a node at
76 the resonator centre and antinodes at the corners. The WG mode is characterised by
77 asymmetric extension/contraction along orthogonal axes producing nodes at the centre and
78 corners of the resonator and antinodes at the edge midpoints. Contour plots of displacement
79 for these modes are shown in Fig. 1. The SE mode was the focus of this study as it is simpler
80 to model and can be implemented with piezoresistive sensing to increase the motional signal
81 [21]. The theoretical resonant frequencies for the experimental resonator size (1400 μm side
82 length) are 3.140 MHz and 2.949 MHz for SE and WG modes, respectively. The
83 experimental resonators were silicon-on-insulator (SOI) devices fabricated using Multi-User
84 MEMS Processes (MUMPs) produced by MEMSCAP [22]. Dimensions and properties of the
85 resonators for the SE mode are shown in Table 1.

86 The symmetric in-plane displacements for SE mode can be described as follows [16] for
87 $x \in [-L/2, L/2]$ and $y \in [-L/2, L/2]$:

88 $u_x(x, t) = U_0 \sin\left(\frac{\pi x}{L}\right) \sin(\omega t)$ Eq. 3a

89 $u_y(y, t) = U_0 \sin\left(\frac{\pi y}{L}\right) \sin(\omega t)$ Eq. 3b

90 where U_0 , L , and ω are the maximum displacement, resonator side length, and modal
 91 frequency of the resonator in the x and y directions at time t . Note that the maximum
 92 displacement, U_0 , has no effect on the sensitivity of the device. The above equations provide
 93 the basis of the spatial sensitivity model.



94 **Fig. 1.** Contour plots of total displacement (as a fraction of maximum unidirectional displacement, U) with
 95 deformed (solid line) and undeformed (dashed line) mode shapes for the (a) square extensional mode and (b)
 96 wine glass mode.

97 **Table 1** Nominal dimensions and characteristics for the SE mode. Resonators were electrostatically forced and
 98 piezoresistively sensed.

Parameter	Unit	Value
Resonator thickness	μm	25
Resonator side length	μm	1400
Capacitance gap	μm	2
Effective mass	μg	114
Effective spring constant	$\text{N } \mu\text{m}^{-1}$	44.4
Natural frequency	MHz	3.140
DC bias	VDC	60
AC power	dBm	0

101 3. Theoretical sensitivity models

102 The spatial sensitivity of a bulk mode resonator is caused by the non-uniform displacement
103 across the resonator body as highlighted by Fig. 1a. For the SE mode, a point mass placed at
104 a corner – an antinode – would experience larger displacements and velocities than an
105 identical point mass placed near the node at the centre of the resonator. Higher velocities
106 result in a larger kinetic energy contribution to the system leading to larger frequency shifts.

107 The Rayleigh-Ritz method can be used, assuming negligible damping, to estimate the
108 resonant frequency of a resonator. The approach assumes the summation of kinetic and
109 potential energies of the system remains constant. The maximum potential and kinetic
110 energies would then be equal and occur when the other is zero. It is possible to extend this
111 result for the inclusion of a new mass to the resonator via an additional kinetic energy term
112 assuming negligible stiffness change (*i.e.* the local resonator mass increases without
113 modifying the elastic behaviour).

114 Three mass addition scenarios were considered in increasing levels of complexity: point mass
115 addition, circular/annular mass addition, and squircular mass addition. The point mass
116 scenario assumes the mass is confined to an infinitesimally small area on the resonator and
117 serves as a proof-of-concept calculation. The circular/annular scenario assumes the mass is
118 spread over a circular (or annular) area with known outer and inner radii. This scenario serves
119 to mimic the “coffee-ring” effect which involves higher concentrations of particle collection
120 along the outer edges of residue [23]. The squircular (a combination of a square and a circle)
121 scenario is meant to account for droplets large enough to interact with the resonator edges.
122 Both the circular/annular and squircular models assumed centred residues but can be
123 modified to account for positional offsets as shown below with a modular squircular
124 approach.

125 The following derivations are for the SE mode only.

126 3.1 No mass addition

127 The no mass addition scenario serves to calculate the initial resonant frequency of a
128 resonator. Treating the resonator as a simple mass spring system, the kinetic and potential
129 energies are:

$$130 \quad KE = \frac{1}{2} M_{\text{eff}} \dot{u}^2 \quad \text{Eq. 4a}$$

$$131 \quad PE = \frac{1}{2} K_{\text{eff}} u^2 \quad \text{Eq. 4b}$$

132 where KE and PE are the kinetic and potential energies for a resonator with effective mass
133 M_{eff} , effective stiffness K_{eff} , local displacement u , and local velocity \dot{u} .

134 For a resonator vibrating at the SE mode, the effective mass and stiffness are given by [16]:

$$135 \quad M_{\text{eff}} = \rho_{\text{Si}} h L^2 \quad \text{Eq. 5a}$$

$$136 \quad K_{\text{eff}} = \pi^2 E_{\text{Si}} h \quad \text{Eq. 5b}$$

137 where ρ_{Si} , h , L , and E_{Si} are the density, thickness, side length, and Young’s modulus of the
138 resonator, respectively.

139 The maximum kinetic and potential energies can be solved using Eq. 3 and Eq. 4 to yield:

$$140 \quad KE_{\text{max}} = \frac{1}{2} M_{\text{eff}} (U_0 \omega_0)^2 \quad \text{Eq. 6a}$$

$$141 \quad PE_{\text{max}} = \frac{1}{2} K_{\text{eff}} U_0^2 \quad \text{Eq. 6b}$$

142

143 Equating the above equations, as per the Rayleigh Ritz method, yields the well-known result:

$$144 \quad \omega_0 = \sqrt{\frac{K_{\text{eff}}}{M_{\text{eff}}}} \quad \text{Eq. 7}$$

145 *3.2 Point mass addition*

146 An additional mass, m , can be added to the system through a kinetic energy term. If the mass
147 is placed at a location (x, y) then the maximum energy equality becomes the following (using
148 Eq. 3 and Eq. 4 as before):

$$149 \quad (U_0 \omega_0)^2 \left[M_{\text{eff}} + m \left(\sin^2 \left(\frac{\pi x}{L} \right) + \sin^2 \left(\frac{\pi y}{L} \right) \right) \right] = K_{\text{eff}} U_0^2 \quad \text{Eq. 8}$$

150 The new resonant frequency, $\omega_{0,\text{pm}}$, is:

$$151 \quad \omega_{0,\text{pm}} = \sqrt{\frac{K_{\text{eff}}}{M_{\text{eff}} + m \left(\sin^2 \left(\frac{\pi x}{L} \right) + \sin^2 \left(\frac{\pi y}{L} \right) \right)}} \quad \text{Eq. 9}$$

152 Sauerbrey's equation, Eq. 10, estimates the frequency shift for mass and stiffness addition.

$$153 \quad \Delta f = \frac{1}{2} \left(\frac{\Delta k}{K_{\text{eff}}} - \frac{\Delta m}{M_{\text{eff}}} \right) f_0 \quad \text{Eq. 10}$$

154 If the stiffness change is negligible (*i.e.* $\Delta k \approx 0$), the sensitivity factor, S , can be solved to
155 satisfy $\Delta f = S f_0$ for an added mass $\Delta m = m [\sin^2(\pi x/L) + \sin^2(\pi y/L)]$ located at a given (x, y)
156 position:

$$157 \quad S_{\text{pm}} = - \frac{m \left(\sin^2 \left(\frac{\pi x}{L} \right) + \sin^2 \left(\frac{\pi y}{L} \right) \right)}{2 \rho_{\text{Si}} h L^2} \quad \text{Eq. 11}$$

158 Eq. 11 is valid for small mass additions and positions within $x \in [-L/2, L/2]$ and
159 $y \in [-L/2, L/2]$. Note that sensitivity is typically an intensive property for a given mode shape
160 whereas the above defined sensitivity factor is an extensive property.

161 *3.3 Circular/annular mass addition*

162 For a mass spread over a significant area, the additional kinetic energy term must be
163 integrated across its entire volume. For an infinitesimally small slice of a quarter circle with
164 mass dm , the kinetic energy dKE is:

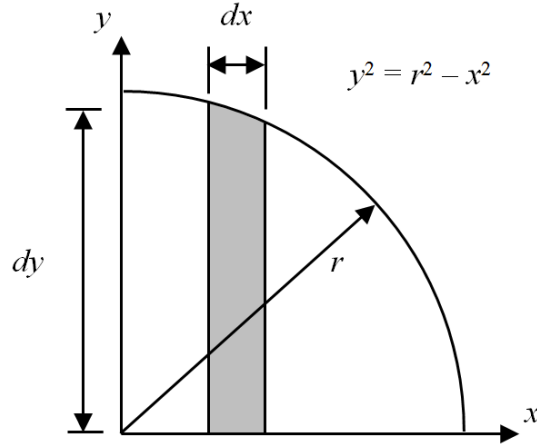
$$165 \quad dKE = \frac{1}{2} \dot{u}^2 dm \quad \text{Eq. 12a}$$

$$166 \quad dKE = \frac{1}{2} \rho_{\text{add}} \delta \dot{u}^2 dA \quad \text{Eq. 12b}$$

167 where ρ_{add} , δ , and dA are the density, thickness, and area of the slice. Note that this assumes
168 uniform thickness and mass distribution across the area. Due to the linearity of integrals, an
169 annular mass can be solved by simple subtraction following the identity:

$$170 \quad \int_{r_i}^{r_o} f(x) dx = \int_0^{r_o} f(x) dx - \int_0^{r_i} f(x) dx \quad \text{Eq. 13}$$

171 Fig. 2 shows the quarter circle of radius r to be integrated in order to solve Eq. 12.



172
173 **Fig. 2.** Quarter circle of radius r with integration slice of area dA shaded.

174 Based on the figure the area dA is:

175
$$dA = \sqrt{r^2 - x^2} dx \quad \text{Eq. 14}$$

176 Integrating the quarter circle in the x -direction from $x = 0 \rightarrow r$ gives the following (assuming
177 $r \leq L/2$):

178
$$KE = \frac{1}{2} \rho_{\text{add}} \delta U_0^2 \cos^2(\omega t) I(r) \quad \text{Eq. 15}$$

179 where

180
$$I(r) \equiv \int_{x=0}^r \sin^2\left(\frac{\pi x}{L}\right) \sqrt{r^2 - x^2} dx \quad \text{Eq. 16a}$$

181
$$I(r) = \dots = \frac{r}{8} \left(\pi r - L J_1\left(\frac{2\pi r}{L}\right) \right) \quad \text{Eq. 16b}$$

182 and $J_1(x)$ is the Bessel function of the first kind.

183 Based on the symmetry of the SE mode, the total kinetic energy for a full annulus (of inner
184 and outer radii r_i and r_o , respectively) in both directions is given by the following. Note that
185 setting $r_i = 0$ yields the result for a circle.

186
$$KE = 4\rho_{\text{add}} \delta U_0^2 \omega^2 \cos^2(\omega t) [I(r_o) - I(r_i)] \quad \text{Eq. 17}$$

187 The maximum energy equality is then:

188
$$(U_0 \omega_0)^2 [M_{\text{eff}} + 4\rho_{\text{add}} \delta U_0^2 \omega_0^2 [I(r_o) - I(r_i)]] = K_{\text{eff}} U_0^2 \quad \text{Eq. 18}$$

189 and the resonant frequency and sensitivity factor are:

190
$$\omega_{0,\text{an}} = \sqrt{\frac{K_{\text{eff}}}{M_{\text{eff}} + 4\rho_{\text{add}} \delta [I(r_o) - I(r_i)]}} \quad \text{Eq.}$$

191 19

192

193
$$S_{\text{an}} = -\frac{2\rho_{\text{add}} \delta [I(r_o) - I(r_i)]}{\rho_{\text{Si}} h L^2} \quad \text{Eq. 20}$$

194 Eq. 20 is valid for small mass additions and residue outer radii $r_o \leq L/2$.

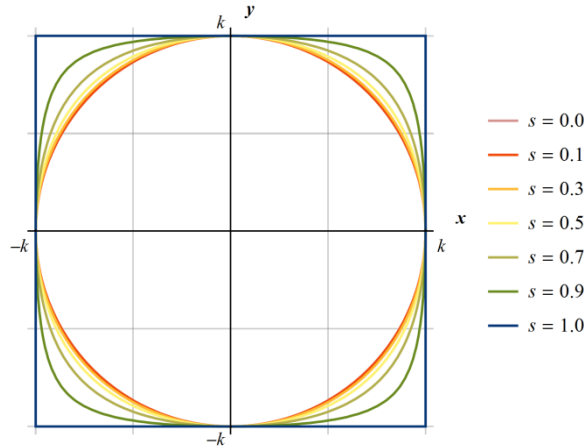
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196 *3.4 Squircular mass addition*

197 A squircle is a geometric shape that shares properties between a square and a circle and it is a
 198 special case of the Lamé curve or superellipse. One possible definition [24] of the squircle in
 199 the x - y plane utilises a squareness factor, s , that ranges from 0 (circle) to 1 (square). A circle,
 200 therefore, is a subset of the general squircle shape. The definition, when centred at the origin,
 201 is given below and plotted in Fig. 3 for varying values of s and a constant k .

202
$$s^2 \frac{x^2}{k^2} \frac{y^2}{k^2} - \left(\frac{x^2}{k^2} + \frac{y^2}{k^2} \right) + 1 = 0$$
 Eq. 21

203



204

205 **Fig. 3.** Centred squircle geometry for varying squareness parameter values (s) with constant k based on the
 206 definition by Guasti [24]. Note that the $s = 0.0$ and $s = 0.1$ cases nearly completely overlap.

207 Following the same procedure for the circle in Section 3.3, the sensitivity factor can be
 208 shown to be:

209
$$S_{sq} = - \frac{2\rho_{add}\delta P(k)}{\rho_{Si}hL^2}$$
 Eq. 22

210 where

211
$$P(k) \equiv k \int_{x=0}^k \sin^2\left(\frac{\pi x}{L}\right) \sqrt{\frac{\left(\frac{x^2}{k^2}\right) - 1}{s^2\left(\frac{x^2}{k^2}\right) - 1}} dx$$
 Eq. 23

212 The function $P(k)$ does not have an analytical solution, unlike $I(r)$, and requires numerical
 213 methods to be solved. Eq. 22 is valid for small mass additions and residue sizes $k \leq L/2$ and
 214 squareness parameters ranging from $0 \leq s < 1$.

215 A summary of the derived theoretical model results is given in Table 2.

216

217 **Table 2** Summary of theoretical sensitivity models for a point mass at location (x, y) , centred circular/annular
 218 mass, and centred squircular mass.

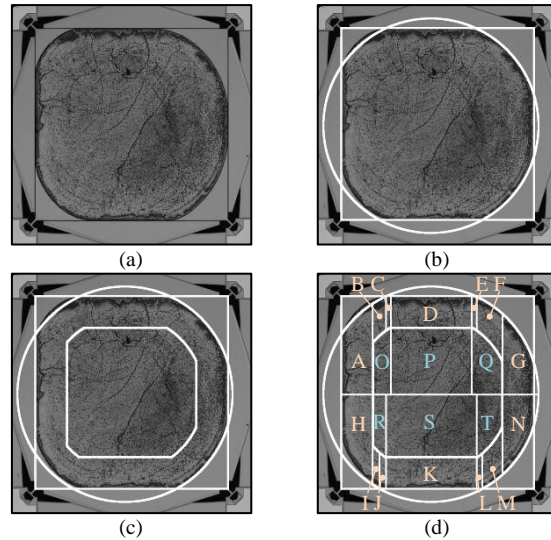
Residue Shape	Sensitivity Factor, S
Point mass	$\frac{m \left(\sin\left(\frac{\pi x}{L}\right)^2 + \sin\left(\frac{\pi y}{L}\right)^2 \right)}{2\rho_{Si} hL^2}$
Centred circle/annulus	$\frac{2\rho_{add} \delta [I(r_o) - I(r_i)]}{\rho_{Si} hL^2}$
Centred squircle	$\frac{2\rho_{add} \delta P(k)}{\rho_{Si} hL^2}$

219 *3.5 Modular approach*

220 While the above squircle definition is a close approximation to the shape remaining after the
 221 evaporation of droplets in contact with the resonator edges (Fig. 4a), a combination of a
 222 square and a circle provides a more accurate fit as it accounts for the longer and non-uniform
 223 linear portions along the resonator edges caused by surface tension. This procedure is also
 224 simpler for image processing and effectively allows for individual squareness parameters at
 225 each corner due to any off-centre alignment.

226 The modular approach involves fitting a square to the resonator and a circle to the residue, as
 227 seen in Fig. 4b, with the origin placed at the centre of the resonator. The circle may extend
 228 past the resonator, be off centre, and allows up to eight intersection points to exist scenario
 229 (*i.e.* the four rounded corners of the squircle shape must exist). A narrowed contour, governed
 230 by a uniform offset from the outer shape, then splits the residue into inner and outer regions
 231 (Fig. 4c). Splitting the residue allows the model to account for the “coffee-ring” effect by
 232 distributing different masses in each region while still assuming homogenous density within
 233 both.

234 Once the residue is split, the intersection points are calculated and the integration regions (up
 235 to twenty in each direction) are defined for both the x - (Fig. 4d) and y -directions. The
 236 integration regions are bounded by the exterior curve (either an arc or a line), the interior
 237 curve (either an arc or a line), or the x - or y -axis between the intersection points. Eq. 12b is
 238 then integrated over these regions and used to solve for the sensitivity factor.
 239



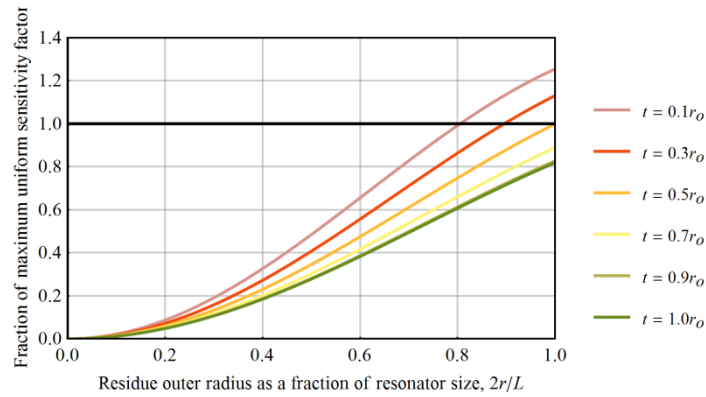
240 **Fig. 4.** Processing steps for modular approach showing (a) the original, aligned image, (b) the fitted square
 241 (resonator) and circle (residue), (c) the contour that splits the residue, (d) the integration regions for the x -
 242 direction in the outer (labelled A through N) and inner (labelled O through T) regions. The interior contour and
 243 all integration regions are for illustrative purposes only (with outer regions exaggerated for clarity) to describe
 244 the method. Similar regions are used for y -direction.

245 **4. Model intercomparison discussion**

246 The point mass model provides a means to examine the relative effect of mass placement but
 247 does not accurately represent the effect of droplet evaporation which consists of a dispersion
 248 of particles. Note that the maximum sensitivity, located at the corner antinodes, of the point
 249 mass model is twice that of the theoretical maximum given by Eq. 2.

250 A comparison of annular ring thicknesses yields the implications of the “coffee-ring” effect.
 251 As the thickness of the ring decreases the mass distribution becomes more concentrated
 252 towards the outer radius of the residue, r_o . Referring to Fig. 1a, this results in more mass
 253 located at areas of high velocity thus increasing the mass loading. The results of running the
 254 circular/annular model at various thicknesses, t , for a constant mass is summarised in Fig. 5.
 255 When $r_o = L/2$ the resonator is more sensitive for small thicknesses ($t < 0.5r_o$) than the
 256 uniform distribution case due to the concentrated placement of the mass as seen previously
 257 with the point mass model. The WG mode shape (Fig. 1b) would result in more pronounced
 258 sensitivity inflation since the antinodes would be better aligned with the ring.

259 Adjusting the squareness factor can simulate the sensitivity effects of placing a large droplet
 260 (or a series of droplets) as discussed above. Fig. 6 shows the sensitivity factors relative to the
 261 uniform thin film deposition case for different sizes (k) and squareness parameter values (s).
 262 The most representative comparison occurs when $k = L/2$ since before the residue touches the
 263 resonator edge the residue would remain circular. Note that as k approaches the size of the
 264 resonator, $L/2$, the $s = 0.0$ cases matches the full circle case ($t = 1.0r_o$) in Fig. 5 and the
 265 $s = 1.0$ case matches the uniform thin film case as expected. Based on the experimental
 266 studies discussed below, the average squareness parameter for the hydrophilic resonator was
 267 estimated to be $s = 0.74 \pm 0.02$ based on 16 processed images with visible residue contact
 268 along the resonator perimeter. This value implies modelling the experimental results as
 269 squircles is significant.



270

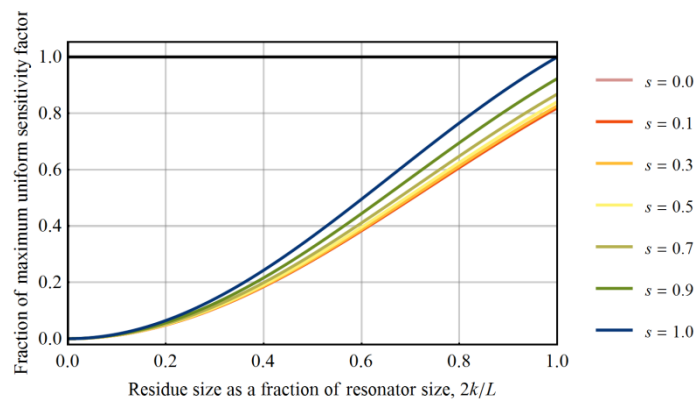
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273

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Fig. 5. Sensitivity factors relative to a uniform thin film deposition for different annulus thicknesses, t , as fractions of the outer radius ranging from $t = 0.1r_o$ (thin ring) to $t = 1.0r_o$ (full disc). Mass kept constant for all sizes (*i.e.* homogenous density varied with changing r_o and t). For small thicknesses ($t < 0.5r_o$) the sensitivity is higher than theoretical maximum as the mass approaches the antinodes only.



275

276

277

278

Fig. 6. Sensitivity factors relative to a uniform thin film deposition for different squariness parameter values ranging from $s = 0.0$ (a circle) to $s = 1.0$ (a square). Mass kept constant for all sizes (*i.e.* homogenous density varied with changing k).

279 5. Experimental studies

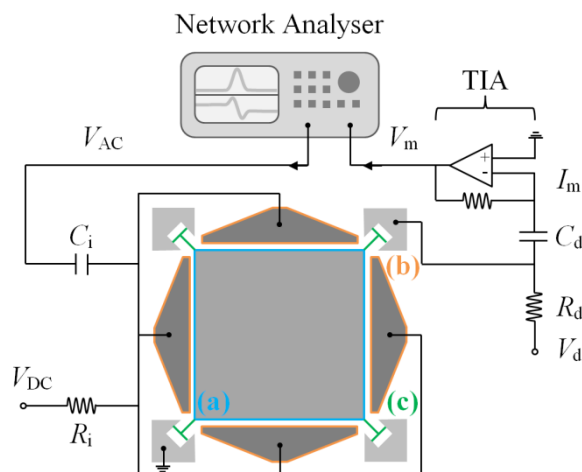
280 A set of experiments were conducted to evaluate the accuracy of the modular approach for
281 calculating sensitivity factors.

282 5.1 Experimental procedure

283 0.5 μL droplets containing a $2.2 \pm 0.1 \text{ ng } \mu\text{L}^{-1}$ suspension of $296 \pm 6 \text{ nm}$ polystyrene latex
284 (PSL) particles (Nanosphere Size Standards, Thermo Fisher Scientific) in High Performance
285 Liquid Chromatography (HPLC) grade water were manually deposited onto 1400 μm square
286 resonators and evaporated in a vacuum chamber. Two suspended resonators, of identical
287 design, were treated to become either hydrophilic or hydrophobic. The hydrophilic surface
288 was produced with low-power O_2 RF plasma (to remove any hydrophobic coatings) while the
289 hydrophobic surface was created using a perfluorodecyltrichlorosilane (FDTS)
290 self-assembled monolayer which has previously been implemented with MEMS surfaces
291 [25].

292 Droplets were placed sequentially on each resonator and evaporated in a vacuum chamber
293 before measuring the resonant frequency while still under vacuum. The resonator surfaces
294 were optically imaged after each measurement. Twenty and ten drops were placed on the
295 hydrophilic and hydrophobic resonators, respectively. The frequency output from the
296 resonator was measured using a network analyser (Agilent 4396B
297 Network/Spectrum/Impedance Analyzer) via piezoresistive sensing of a one-port capacitive

298 forcing arrangement (Fig. 7). Frequency measurements, taken over a span of 1 kHz centred at
 299 the peak, were recorded after a set time to minimise temperature drift induced by
 300 piezoresistive sensing and allow for pressure stabilisation within the chamber. The
 301 experimental sensitivity factor, S_i , discussed in subsequent sections was calculated for each
 302 droplet i based on a measured frequency, f_i , following the definition $S_i = (f_i - f_0)/f_0$.



303
 304 **Fig. 7.** Circuit schematic for one-port capacitive forcing with piezoresistive sensing highlighting the (a)
 305 resonator, (b) electrodes, and (c) anchors (adapted from [26]). An input voltage consisting of AC (V_{AC}) and DC
 306 (V_{DC}) components is sent to actuate all four electrodes. The output motional current (I_m) is then sensed through
 307 one of the anchors with the diagonally opposite anchor being grounded. The motional current is then passed to
 308 the network analyser via a transimpedance amp (TIA) to measure the S_{21} parameter.

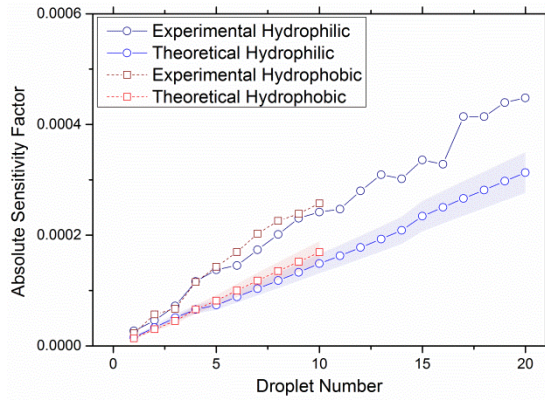
309 The above method was previously shown [15] to provide consistent (yet elevated) mass
 310 addition due to the presence of contaminant particles which was accounted for based on
 311 larger scale mass experiments as discussed in Section 5.3.

312 5.2 Model comparisons

313 Each image was analysed using the modular approach described in Section 3.5 to estimate the
 314 relative frequency shift induced by each droplet. Image processing was performed using
 315 simple geometric relations and the GNU Image Manipulation Program (GIMP) [27]. The
 316 “coffee-ring” thicknesses were 0.024 and 0.040 of the effective residue radius for hydrophilic
 317 and hydrophobic surfaces, respectively, based on average values for each set of images as
 318 analysed through GIMP. Following studies by Yunker *et al.* [23], which corroborate the
 319 “coffee-ring” thicknesses above, 98.5% of the total mass was distributed in the “coffee-ring”
 320 for each model run. The total mass per droplet used in the model (approximately 5.2 ng)
 321 included factors accounting for contaminants (further explained in Section 5.3) in the solution
 322 and potentially trapped water between closely packed particles. The model assumes the total
 323 added mass is redistributed after each droplet following the “coffee-ring” distribution.

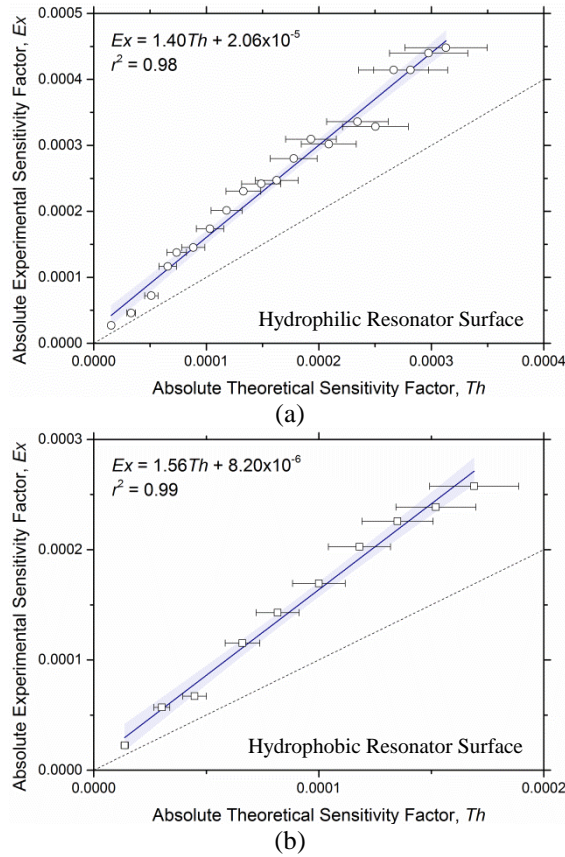
324 Recalling that the theoretical model assumes homogenous distributions, it should be
 325 recognised that the any heterogeneity of the mass distribution could influence the following
 326 comparisons. Modelling this heterogeneity is quite difficult, and the true response depends on
 327 the mass location relative to the mode shape in a similar fashion to Fig. 5 and Fig. 6.

328 The comparison between measured (with capacitive feedthrough removed following Lee *et al.*
 329 [17]) and modelled results on a per droplet basis are shown in Fig. 8 while a direct
 330 comparison via correlation plots is shown in Fig. 9. Both correlation plots show strong
 331 correlation with r^2 values above 98% and slopes implying gain errors on the order of 1.5.
 332 Slopes greater than 1 suggest the existence of additional unexpected mass, on the order of 2
 333 to 3 ng, that may be due in part to discrepancies in solution preparation procedures between
 334 resonator testing and the larger scale microbalance studies (Section 5.3).



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Fig. 8. Absolute experimental and theoretical sensitivity factors for both resonator surface treatments on a per droplet basis. Experimental results show a distinctly increased slope implying more mass was added than expected. The theoretical model assumes a mass addition of 5.2 ng per droplet (including contaminants). Filled areas represent 95% confidence interval of fit.



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Fig. 9. Correlation plots for (a) hydrophilic and (b) hydrophobic resonators between experimental and theoretical sensitivity factors showing a strong linear relationship with a small slope and a factor of approximately 1.5 difference between the model and experimental results. Experimental results have capacitive feedthrough analytically removed. The theoretical model assumes a mass addition of 5.2 ng per droplet (including contaminants). Filled areas represent 95% confidence interval of fit.

Inconsistent slopes between the resonators could imply differences in mass distribution, residue thickness, or particle stacking (as discussed in Section 5.4). Manufacturing discrepancies from nominal resonator dimensions may also have a minor influence on the slopes. The non-zero y-intercepts in the correlations highlight the uncertainty in the slopes as they should ideally be zero. Note that the y-intercept for the hydrophobic resonator is within zero when considering the 95% confidence interval.

352 Using the slopes from each correlation to orientate data on the same scale, the experimental
353 and theoretical relative frequency shifts (*i.e.* sensitivity factors) were plotted to show the
354 drop-by-drop trends in Fig. 10. There are three general scenarios seen during the deposition
355 of particles: residue growth, uniform mass addition, and particle stacking.

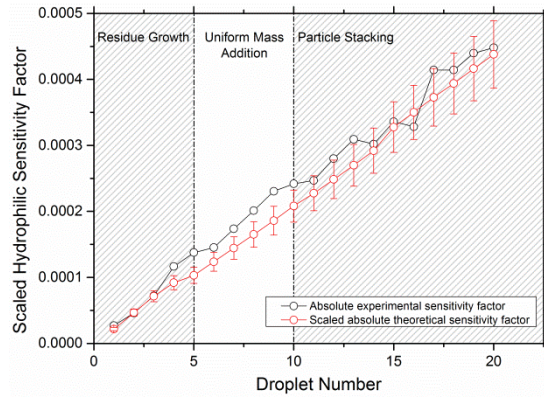
356 The residue growth scenario is described by an increasing residue radius over sequential
357 drops. This scenario experiences the largest spatial sensitivity as the droplet is both
358 expanding and adjusting its location as particles are rearranged. Fig. 11 shows the residue
359 growth and highlights a transition after the fifth droplet for both resonators after which the
360 radius remains stable. Fig. 12 shows a selection of images of the resonator surface
361 corresponding to the initial droplet (Drop 1), the transition (Drop 5), and the final residue
362 (Drop 20, 10) for both resonators. Note that the general residue shape does not change
363 between the transition and final images but there is a distinct increase in particle
364 concentration. The concept of spatial sensitivity dictates that the slope magnitude should
365 reduce after the transition (*i.e.* the fifth droplet) as the frequency shift will solely be mass
366 based. Experimental results corroborate this expectation as the slope magnitudes reduced
367 from $(2.9 \pm 0.6) \times 10^{-5} \text{ droplet}^{-1}$ to $(2.1 \pm 0.2) \times 10^{-5} \text{ droplet}^{-1}$ and from $(3.0 \pm 0.5) \times 10^{-5} \text{ droplet}^{-1}$
368 to $(2.1 \pm 0.4) \times 10^{-5} \text{ droplet}^{-1}$ for the hydrophilic and hydrophobic resonators at confidence
369 levels of 90% and 80%, respectively.

370 After the transition, there is a scenario of uniform mass addition which the model expects to
371 be relatively constant. This holds true for the experimental hydrophobic data, but the
372 hydrophilic data shows significant fluctuations past the tenth droplet. The expected cause of
373 these fluctuations is the vertical stacking of particles after each droplet is evaporated as the
374 higher stacked particles will have diminished energy influences based on their attachment
375 stiffness. Particle stacking was previously shown [15] to take place during droplet deposition.
376 Since the theoretical model assumes a constant energy contribution per mass added it does
377 not account for these fluctuations.

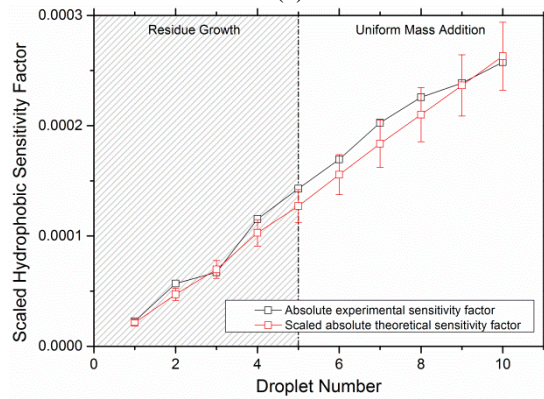
378 The spatial sensitivity model provides the most information prior to the residue stabilising in
379 shape and accounts for some of the experimental fluctuations seen during this region. For
380 example, the shift between the third and fourth drop on the hydrophobic resonator is well
381 captured by the model. The fourth hydrophobic droplet saw a sudden residue expansion,
382 captured in the residue sizes from Fig. 11, resulting in the substantial frequency shift. In
383 general, the sensitivity model appears to be applicable regardless of surface treatment as
384 overall trends were consistent and local trends within the residue growth region followed the
385 experimental results well.

386 An additional detail presented by Fig. 10 is that once the gain error is accounted for the
387 experimental results and theoretical results follow quite well (and generally within
388 uncertainty) implying that the main discrepancy is likely due to a consistent unaccounted
389 mass in each droplet.

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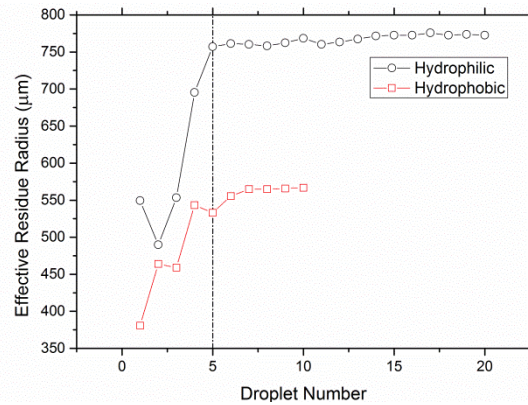


(a)



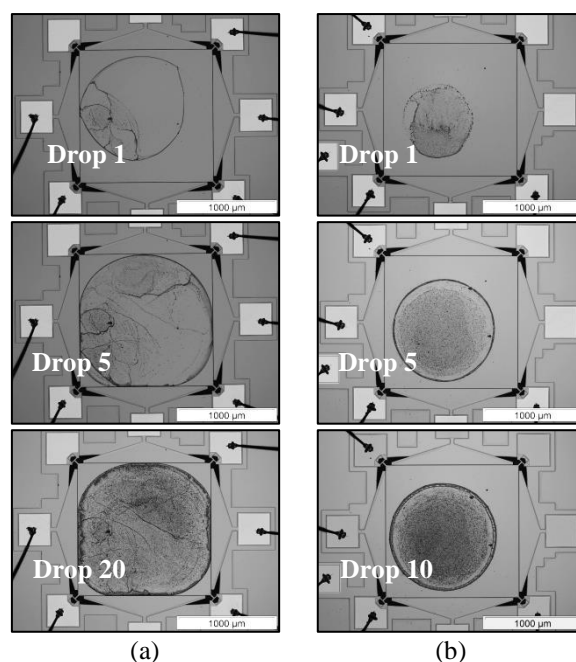
(b)

391 **Fig. 10.** Sensitivity factors on a per droplet basis relative to original, unloaded resonant frequency using
 392 experimental and theoretical results for the (a) hydrophilic and (b) hydrophobic resonators. Theoretical results
 393 adjusted to the experimental scale using correlation slopes as given in Fig. 9.



394 **Fig. 11.** Residue radius growth rate per droplet. Radius stabilises for both resonators (hydrophilic and
 395 hydrophobic) at approximately the fifth droplet. The hydrophilic radius is based on the modular approach and
 396 describes a squircle rather than a perfect circle.
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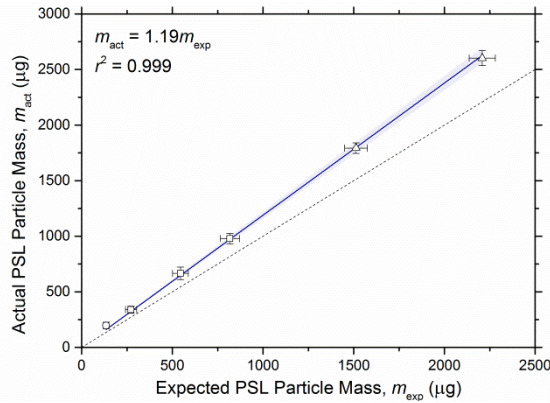


400 **Fig. 12.** Selected images after measurement for (a) hydrophilic and (b) hydrophobic resonators. The first drop
 401 shows the start of the residue growth for both resonators. The fifth drop for both resonators is the point when the
 402 residue size stopped significantly growing as per Fig. 11. The twentieth and tenth drop for the hydrophilic and
 403 hydrophobic resonators, respectively, show the final resonator surfaces with a similar area to the fifth drop but
 404 noticeably larger concentrations of particles.

405 5.3 Examining contamination factor

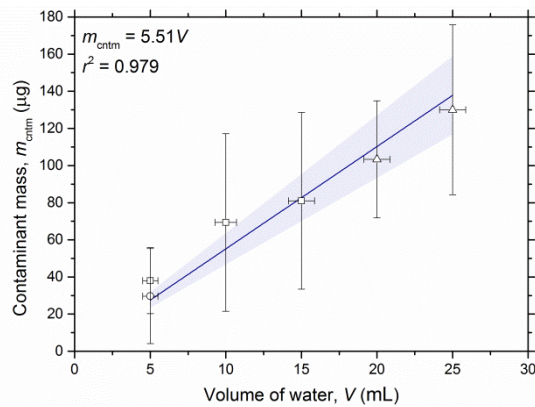
406 Larger scale mass experiments were conducted, using a mechanical microbalance (M5,
 407 Mettler Inc.), to quantify the additional mass deposited when using a suspension of PSL
 408 particles and HPLC grade water. The procedure separated a set of twelve vials, previously
 409 cleaned via methanol sonication and baking, into three groups: six vials for a PSL particle
 410 and HPLC grade water solution, three vials for HPLC grade water only, and three vials left to
 411 a control (*i.e.* empty). Volumes of 5 mL were pipetted into each non-control vial and left to
 412 evaporate under a nitrogen air flow before measuring the mass change. Three different
 413 concentrations of PSL particles were used in two different sets of vials. In the first vial set, a
 414 concentration of $27 \pm 1 \mu\text{g mL}^{-1}$ was used for a single measurement. In the second vial set,
 415 three measurements using a concentration of $54 \pm 3 \mu\text{g mL}^{-1}$ were followed by two
 416 measurements using a concentration of $139 \pm 7 \mu\text{g mL}^{-1}$.

417 The results of these experiments showed a significant deviation from a 1:1 relationship
 418 between expected and actual PSL particle mass as shown in Fig. 13. Similarly, Fig. 14 shows
 419 significant contamination from the water. A deposited mass correction can be completed
 420 assuming a percentage contamination associated with PSL particle mass (slope from Fig. 13)
 421 and a volume based contamination for the HPLC grade water measurements (slope from Fig.
 422 14). The correction equation based on these slopes is presented in Fig. 15 with the original
 423 data points included to show good agreement. Extending this relationship to the original 0.5
 424 μL droplets containing 1.1 ng of PSL particles, the corrected mass is $4.0 \pm 0.4 \text{ ng}$ with
 425 approximately 2/3 of the mass coming from water contamination. SEM images, shown in Fig.
 426 16, corroborate that both the stock PSL solution and HPLC grade water contain
 427 contaminants. Note that surfactants in the stock PSL particle solution were expected to only
 428 make up 0.142% of the total PSL particle-related mass.



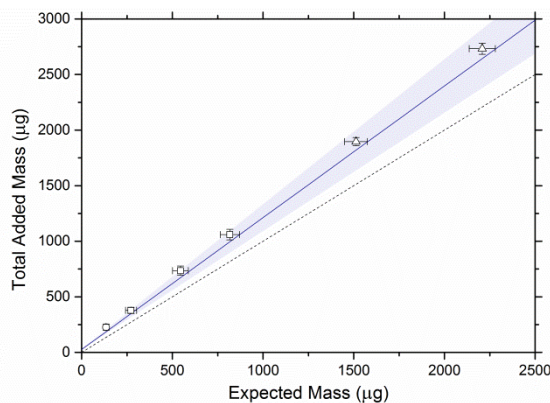
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430 **Fig. 13.** Correlation plot between actual and expected PSL particle mass addition. Expected mass is based on
 431 solution concentrations; actual mass is the mass difference between PSL particle-containing and water only
 432 vials. A strong linear relationship implies 19% more mass was added than expected from the PSL solution alone
 433 (does not account for water contamination). Symbols correspond to PSL concentrations (\circ , \square , and Δ describe
 434 $27 \pm 1 \mu\text{g mL}^{-1}$, $54 \pm 3 \mu\text{g mL}^{-1}$, and $139 \pm 7 \mu\text{g mL}^{-1}$, respectively). Filled area shows 95% confidence interval
 435 of fit. Dashed line represents 1:1 ratio.



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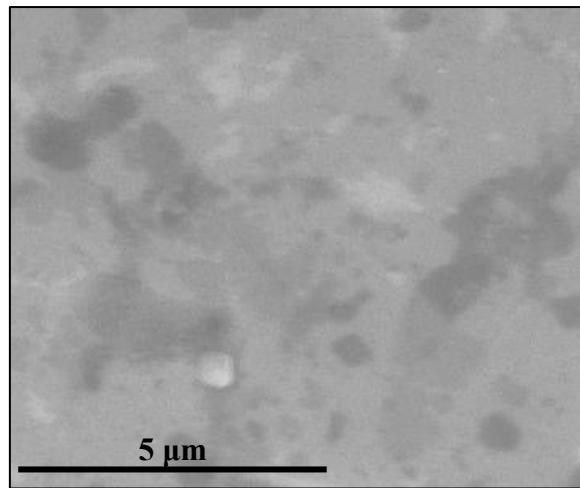
437 **Fig. 14.** Correlation plot between water contamination mass and deposited HPLC grade water. Contamination
 438 mass is based on the mass difference between water only vials and the control vials. A strong linear relationship
 439 implies $5.51 \mu\text{g}$ of contaminants in the water is added per mL. Symbols correspond to PSL concentrations (\circ , \square ,
 440 and Δ describe $27 \pm 1 \mu\text{g mL}^{-1}$, $54 \pm 3 \mu\text{g mL}^{-1}$, and $139 \pm 7 \mu\text{g mL}^{-1}$, respectively). Filled area shows 95%
 441 confidence interval of fit.



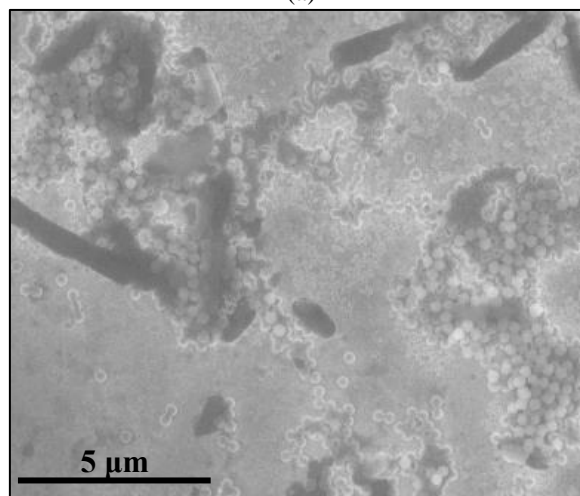
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443 **Fig. 15.** Correlation plot between the total added mass and expected (*i.e.* PSL particle) mass. Fitted line
 444 describes predictive equation (with 95% confidence interval) based on slopes from Fig. 13 and Fig. 14. Symbols
 445 correspond to PSL concentrations (\circ , \square , and Δ describe $27 \pm 1 \mu\text{g mL}^{-1}$, $54 \pm 3 \mu\text{g mL}^{-1}$, and $139 \pm 7 \mu\text{g mL}^{-1}$,
 446 respectively). Dashed line represents 1:1 ratio.

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(a)

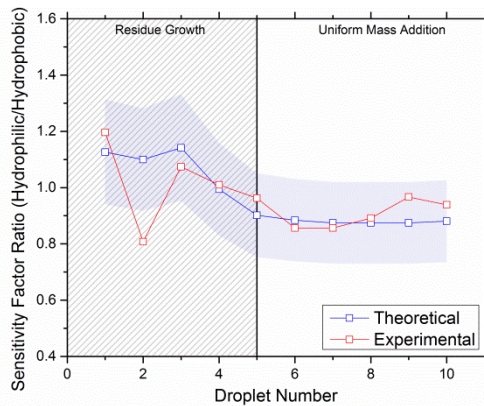


(b)

448 **Fig. 16.** SEM images of an untreated, hydrophilic silicon resonator surface with evaporated (a) HPLC grade
449 water only and (b) PSL particles and HPLC grade water. The contamination seen in (a) also covers the surface
450 of the resonator surface in (b). The dark, cylindrical particles in (b) are contaminants (PSL particles are white
451 and spherical).

452 *5.4 Comparing Hydrophilic and Hydrophobic Coatings*

453 Based on the early model runs shown in Fig. 6 it would be expected that the hydrophilic
454 sensitivity would be higher than the hydrophobic sensitivity since the residue has reached the
455 more sensitive regions of the resonator. However, as shown in Fig. 17, both the experimental
456 and theoretical results show disagreement with this expectation. Past the residue growth
457 region, the hydrophilic sensitivity is approximately 90% of the hydrophobic sensitivity which
458 is partially explained by the assumptions made for mass distribution. The model runs in Fig.
459 6 assume a uniform mass distributed across the entire residue while the modular approach in
460 Fig. 17 accounts for the “coffee-ring” in a way that is also influenced by the size of the
461 residue. That is, for smaller residue sizes the total area of the “coffee-ring” is smaller thus
462 causing a higher mass density along the outer edge than for larger residues. Another
463 influential factor is the particle stacking and conglomeration that is more prevalent on the
464 hydrophilic resonator surface (Fig. 16b) which would lead to reduced effective masses and a
465 ratio less than one.



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Fig. 17. Ratios of hydrophilic sensitivity to hydrophobic sensitivity on a per droplet basis for both theoretical and experimental results. After the initial residue growth stage, both theoretical and experimental results fluctuate around a ratio of 0.9. Filled area shows 95% confidence interval of theoretical model.

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6. Conclusions

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Bulk acoustic mode resonators show potential for high sensitivity mass sensing but consideration of their spatial sensitivity is necessary. Sensitivity to both mass and spatial distribution on the resonator was modelled and confirmed experimentally for the square extensional mode using piezoresistive sensing of electrostatically actuated MEMS resonators.

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Three analytical sensitivity models were introduced with varying levels of complexity to investigate the implications of shape and area on sensitivity for a specific actuation mode. A modular approach was used to aptly compare the spatial sensitivity model to experimental results.

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Three distinct stages of sensitivity were introduced covering initial residue growth, uniform mass addition, and particle stacking. The effects were observed regardless of surface treatment and based primarily on mass addition and distribution. The hydrophilic surface showed a larger degree of particle stacking and conglomeration when inspected with an SEM.

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Potential improvements to the presented model focus around the assumptions made during the derivations. Incorporating non-homogeneous densities and non-uniform residue thicknesses would allow for a more accurate modelling potential for situations such as the “coffee-ring” effect (beyond the current approach). Furthermore, examining the particular case of a coupled resonator-particle system [28] for low particle attachment stiffness may explain the large fluctuations in resonant frequency during the particle stacking phase.

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Experimentally, using a cleaner (*i.e.* fewer contaminants) particle source would provide more accurate comparisons and reproducible results since remaining the differences can be explained by a simple gain error.

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Acknowledgements

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